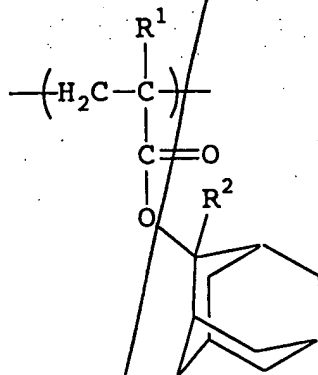
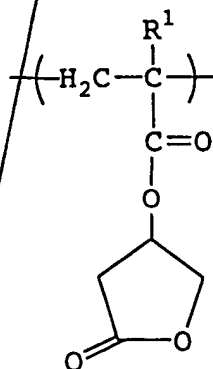


the component (A) being a copolymer consisting of the monomeric units of

(a1) from 30 to 60% by moles of 2-alkyl-2-adamantyl (meth) acrylate units having the formula:

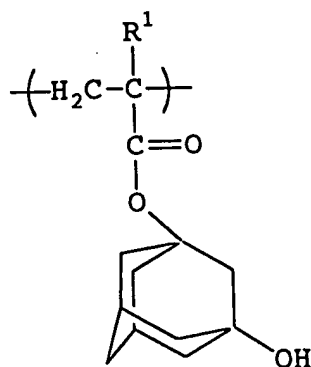


(a2) from 20 to 50% by moles of 2-oxooxapentyl (meth) acrylate units having the formula:



(a3) from 20 to 40% by moles of 1-hydroxyadamantyl (meth) acrylate units.

13. (New) The positive-working photoresist composition as claimed in claim 12¹ in which the monomeric unit (a3) is a unit represented by the general formula



in which R¹ is a hydrogen atom or a methyl group.

3 14. (New) The positive-working photoresist composition as claimed in claim 12¹ in which the component (B) is an onium salt compound having a fluorinated alkylsulfonic acid ion as the anionic counterpart.

Q 15. (New) The positive-working photoresist composition as claimed in claim 12¹ in which the component (C) is a mixture of (c1) propyleneglycol monomethyl ether acetate, ethyl lactate or a combination thereof and (c2) γ -butyrolactone in a mixing proportion of 70:30 to 95:5 by weight.

16. (New) The positive-working photoresist composition as claimed in claim 12¹ which further comprises (D) from 0.01 to 0.2 part by weight of a secondary or tertiary aliphatic amine compound per 100 parts by weight of the component (A).

5 17. (New) The positive-working photoresist composition as claimed in claim 16¹ in which the component (D) is a trialkanol amine.
